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	Application No. Applicant(s)  09/498,375 ITO ET AL.		
Notice of Allowability			
	Examiner	Art Unit	
	Rodney G. McDonald	1753	
The MAILING DATE of this communication appeal All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R	(OR REMAINS) CLOSED in a community or other appropriate community in the community of the c	this application. If not inclu nication will be mailed in du	ided e course. <b>THIS</b>
1. This communication is responsive to <u>4-7-04</u> .			
2. ☑ The allowed claim(s) is/are <u>1-30,33-42 and 73</u> .			
3. $igotimes$ The drawings filed on <u>23 April 2003</u> are accepted by the E	xaminer.		
<ul> <li>4. Acknowledgment is made of a claim for foreign priority unally a) All b) Some* c) None of the:</li> <li>1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority do International Bureau (PCT Rule 17.2(a)).</li> <li>* Certified copies not received:</li> </ul>	e been received. e been received in Application	n No	cation from the
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		a reply complying with the r	requirements
5. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which giv	nitted. Note the attached EXAI es reason(s) why the oath or	MINER'S AMENDMENT or declaration is deficient.	NOTICE OF
<ol> <li>CORRECTED DRAWINGS ( as "replacement sheets") muse (a)  including changes required by the Notice of Draftspers 1)  hereto or 2)  to Paper No./Mail Date</li> <li>(b)  including changes required by the attached Examiner Paper No./Mail Date</li> <li>Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in the street of the sheet of</li></ol>	son's Patent Drawing Review . s Amendment / Comment or i	in the Office action of a drawings in the front (not t	he back) of
7. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT	sit of BIOLOGICAL MATE FOR THE DEPOSIT OF BIO	RIAL must be submitted LOGICAL MATERIAL.	. Note the
Attachment(s)  1. Notice of References Cited (PTO-892)  2. Notice of Draftperson's Patent Drawing Review (PTO-948)  3. Information Disclosure Statements (PTO-1449 or PTO/SB/C Paper No./Mail Date  4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview Sur Paper No./N 08), 7. ☐ Examiner's A	Mail Date Amendment/Comment Statement of Reasons for A	llowance
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## **REASONS FOR ALLOWANCE**

The following is an examiner's statement of reasons for allowance:

Claims 1-14 are allowable over the prior art of record because the prior art of record does not teach the claimed subject matter with the removal claw having an inclined section configured to go into a section between a rear surface of the substrate and a top surface of the substrate holder to mechanically peel off the adsorbed substrate from the substrate holder.

Claims 15-18 and 73 are indicated as being allowable over the prior art of record because the prior art of record does not teach the claimed subject matter including a groove section which extends from a portion where said substrate holder contacts said substrate when said substrate holder is holding said substrate to a portion where said substrate holder does not contact said substrate when said substrate holder is holding said substrate; and a porous member which can allow air to pass through provided within said groove section in which the surface of the porous member is at a same level as the surface of the substrate holder.

Claims 19-22 are allowable over the prior art of record because the prior art of record does not teach the optical disk substrate film-formation apparatus having the substrate holder located between the film-formation chamber in which film formation for a substrate is performed and a substrate carriage chamber in which a pressure is maintained at a lower level than in the film-formation chamber and wherein the throughhole directly communicates with air within the substrate carriage chamber.

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Claims 23-29 are allowable over the prior art of record because the prior art of record does not teach an optical disk substrate film-formation apparatus comprising a substrate holder which holds thereon an optical disk substrate as an object for film formation, an inner mask which masks a specified area on an inner side of the optical disk; and an outer mask which masks a specified area on an outer side of the optical disk; wherein the inner mask and the outer mask being used for forming a thin-film on a surface of the optical disk substrate, said substrate holder having, a substrate holding section which contacts the optical disk substrate on the rear surface of the optical disk substrate but in a portion where the thin-film has been formed on the front surface, wherein the substrate holding section contact the optical disk substrate in the portion extending between a line which is 2 to 10 mm on the outer side of an edge of the inner mask ant a line which is 0.5 to 5 mm on the inner side of an inner edge of the outer mask.

Claims 30 and 33-42 are indicated as being allowable over the prior art of record because the prior art of record does not teach an optical disk substrate film-formation apparatus used for sputter film formation in which a laminated film is formed by combining any one or two or more of a reflection layer, a recording layer, a protection layer, or a dielectric body layer on a disk substrate in an optical disk manufacture step comprising: a gas supply section for introduction of gas in the substrate holder side in a limited portion between a substrate setting surface of the substrate holder and a film-formed substrate, and at least a closed space section in the area formed in the substrate holder side because of contact between the substrate and substrate holder,

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wherein gas is supplied from the gas supply section during a period from a time point when sputter film formation is finished until a time point when a substrate is carrier out, and wherein the gas supplied from the gas supply section is also used as vent-gas for a load lock chamber between atmosphere for inserting a substrate into or carrying out from the optical disk substrate film-formation apparatus and vacuum.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to Rodney G. McDonald whose telephone number is 571-272-1340. The examiner can normally be reached on M- Th with Every other Friday off.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nam X. Nguyen can be reached on 571-272-1342. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Rodney G. McDonald Primary Examiner Art Unit 1753

RM April 12, 2004